



## 2D Modeling - Gas Phase

Maurizio Rondanini, Carlo Cavallotti

*Dip. Chimica, Materiali e Ingegneria Chimica "G. Natta" – Politecnico di Milano*



# Outline

- Model structure
- Summary of previous results and problems
- Plasma Model improvements
- Results





# Features of the Model

2 D plasma discharge model

2D Electronic density, electric field

2 D model of gas phase and surface chemistry model

Gas phase composition

Ions + radicals

Surface fluxes

Growth Rates

UniMib

Reaction rates

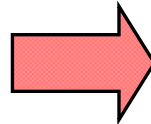
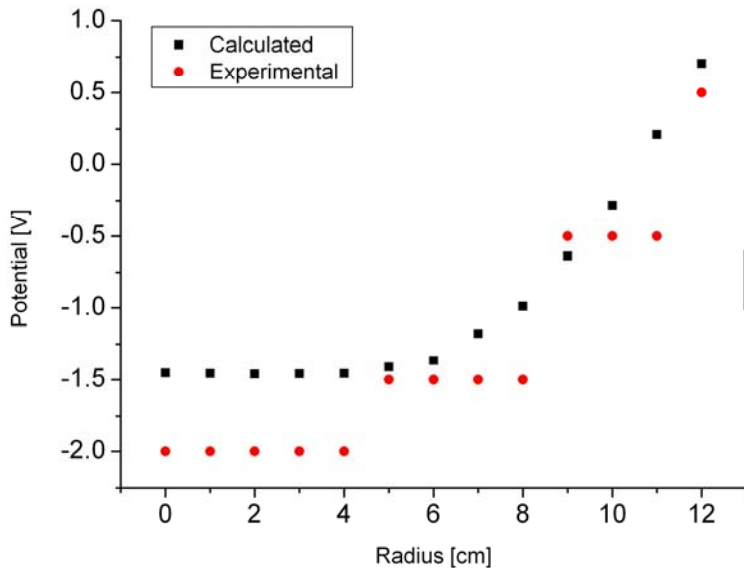
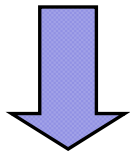
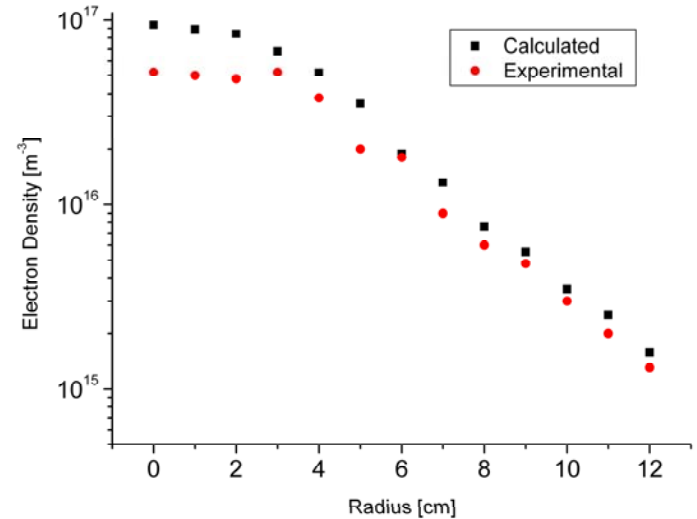
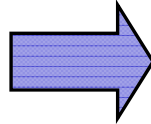
Literature + Polimi

Gas phase and surface kinetic mechanism of elementary reactions



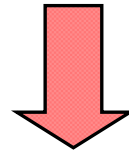
# Plasma Discharge

Model validated on pure Ar plasma discharge



2D Gas Model

Problem: comparison with ion experimental concentrations





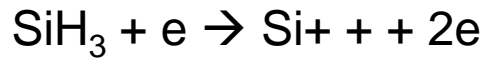
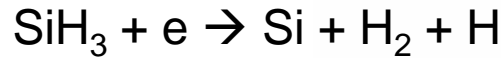
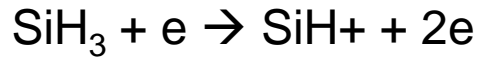
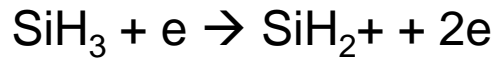
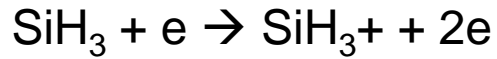
# Features implemented for Aix

Pos A    B    C

- Introduction of new reactions:

SiH<sub>3</sub>, SiH<sub>2</sub>, SiH and H ionization and dissociation

e.g.



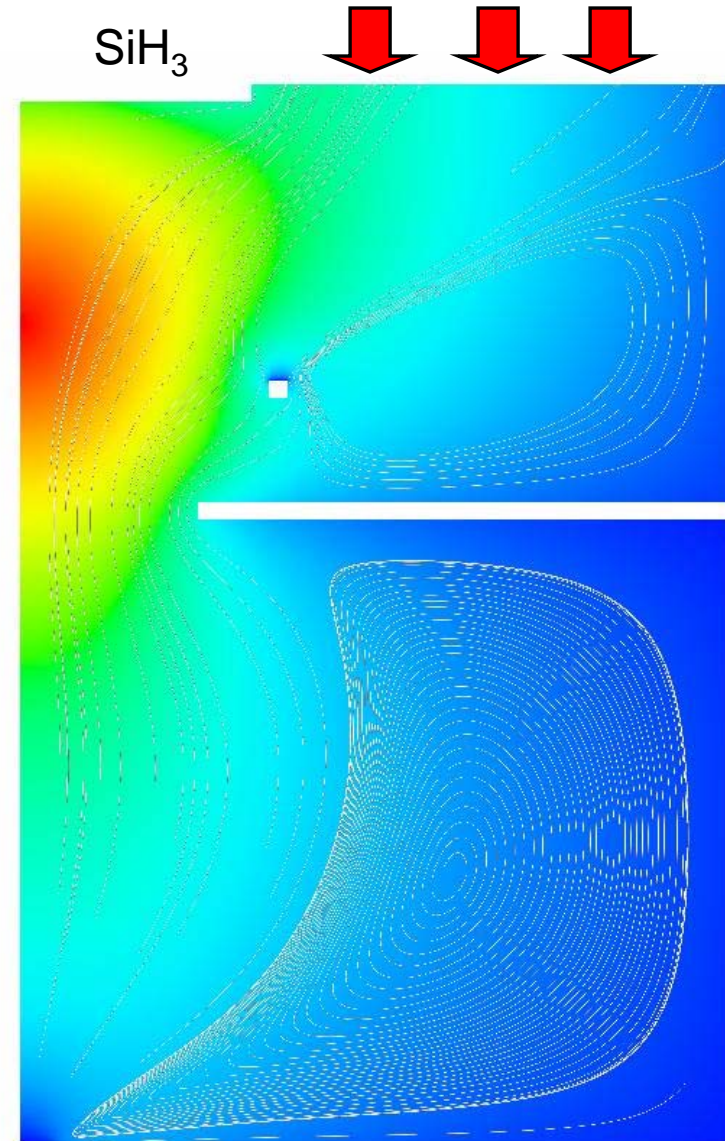
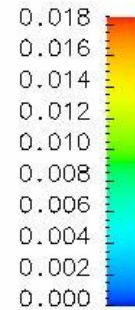
New Boundary conditions at inlets

- Flux boundary condition for inlet 2:

$$D_i \nabla C_i = \text{Flux in}$$

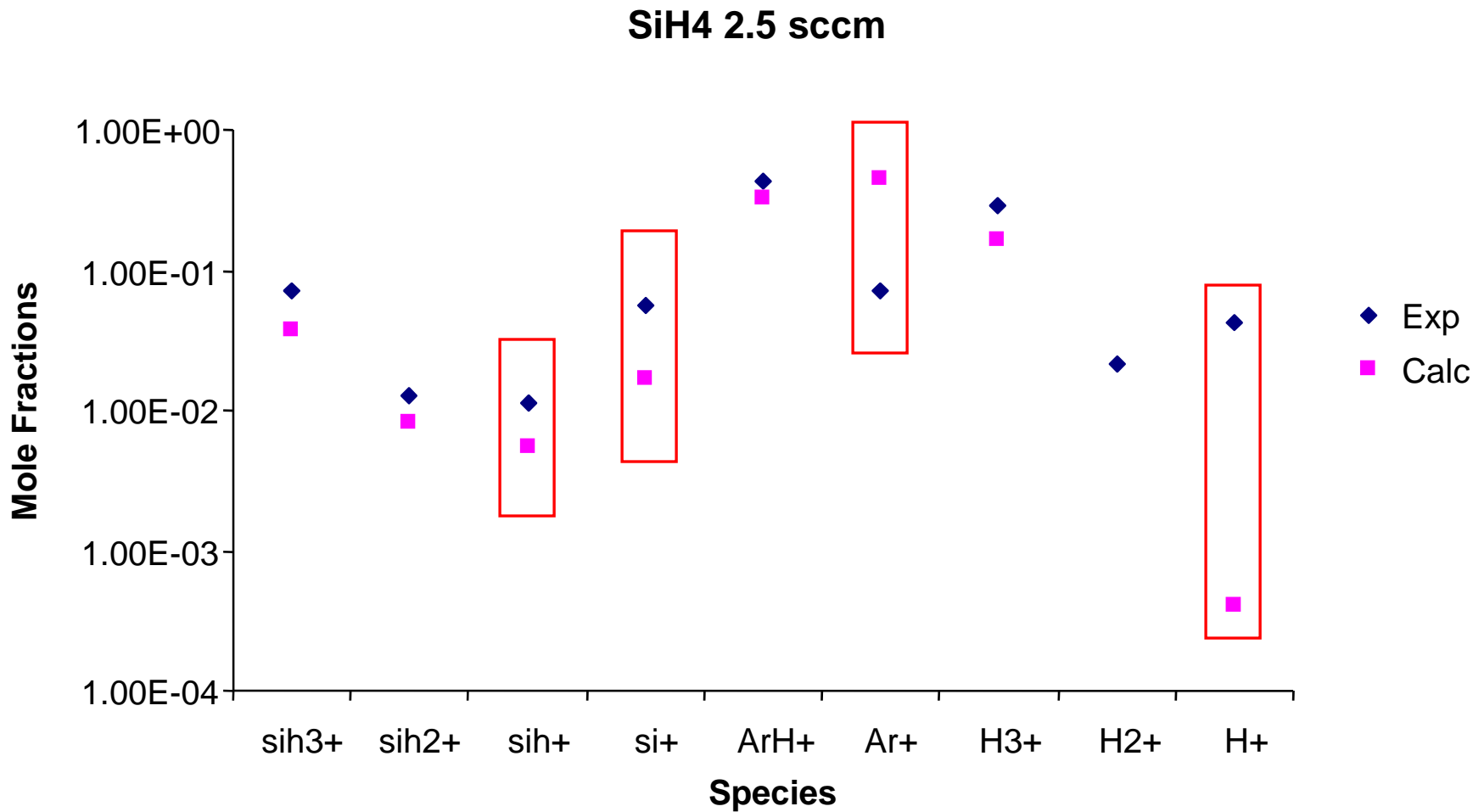
- inlet 1 (→ Dankwerts BC:

$$v_i C_i^+ + D_i \nabla C_i = v_i C_i$$



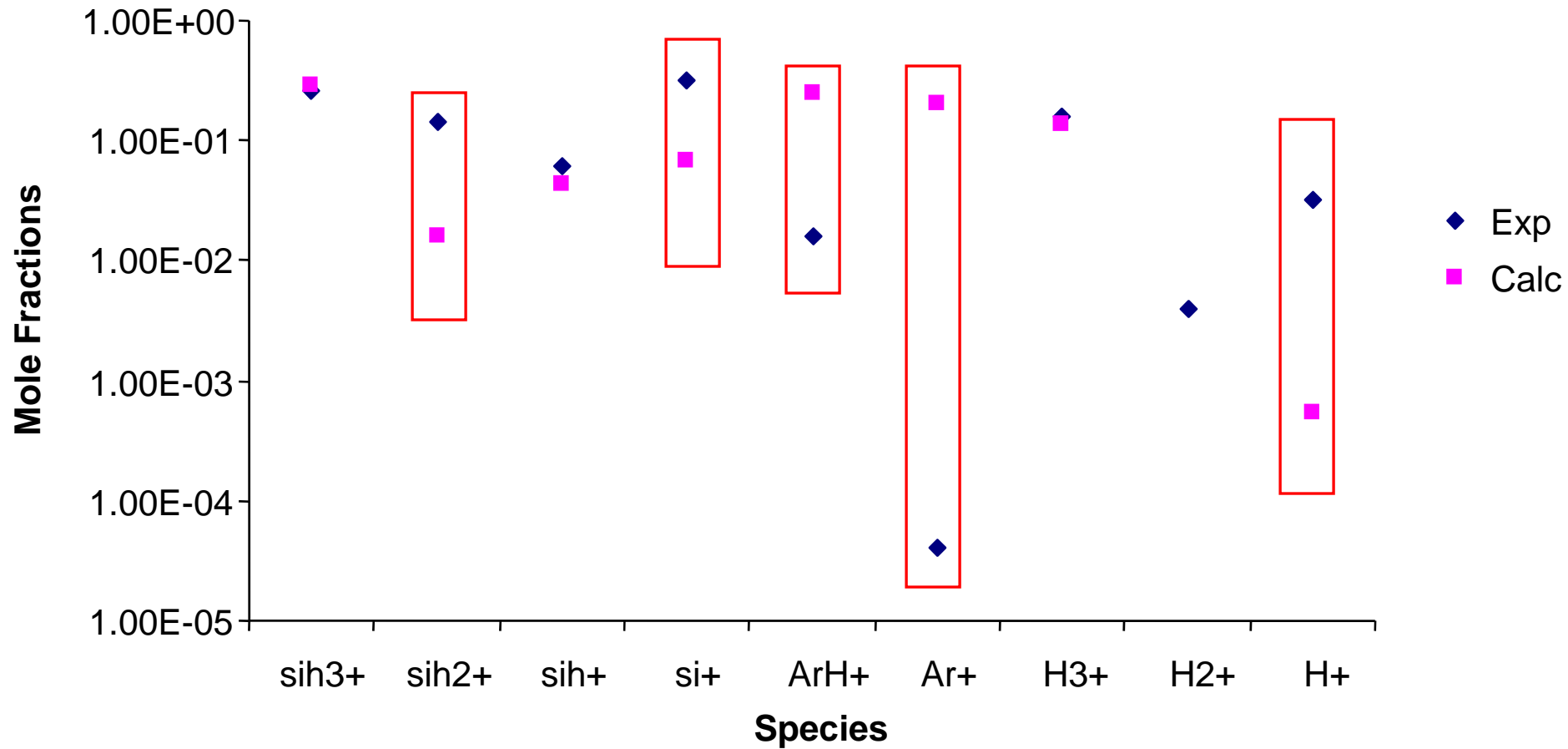


# Results: ion concentrations – 2.5 sccm SiH4 pos B



# Results: ion concentrations 20 sccm pos B

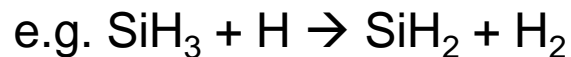
## SiH<sub>4</sub> 20 sccm





## Improvement of model after AIX

- Elimination of reactions at plasma reactor walls
- Assumption that the mass spectrometer perturbs the eedf in front of the orifice so that there is a volume where electronic reactions are not active. Non reactive volume fitted over exp  $\text{ArH}^+ / \text{H}_3^+$  ratio measured for Ar/H<sub>2</sub> plasma (only one fitting)
- Introduction of new reactions involving H induced decomposition of SiH<sub>x</sub> and SiH<sub>3</sub><sup>+</sup> species:



Low pressure kinetic constant calculated with RRKM/ME approach on high level ab initio data



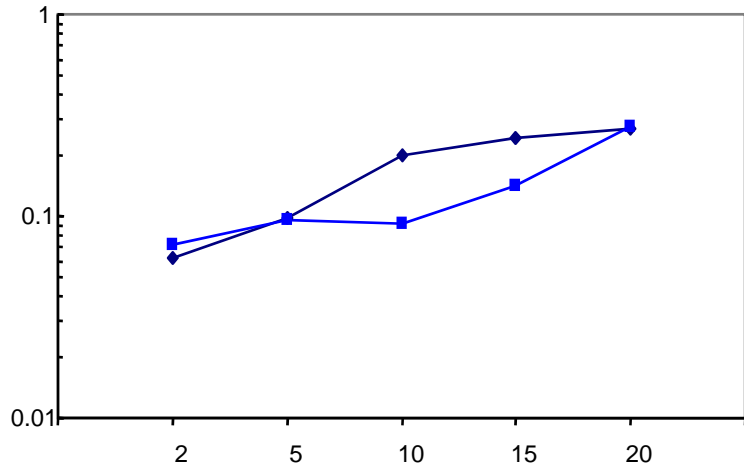




# Last Results – position B

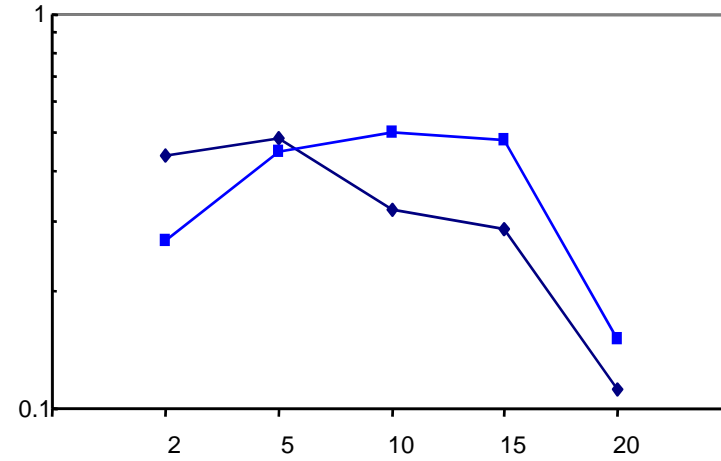
SiH<sub>3</sub><sup>+</sup>

◆ Calc  
■ Exp



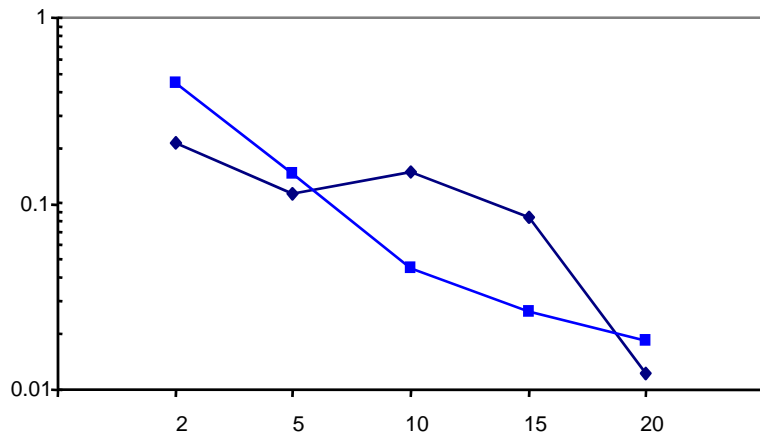
H<sub>3</sub><sup>+</sup>

◆ Calc  
■ Exp



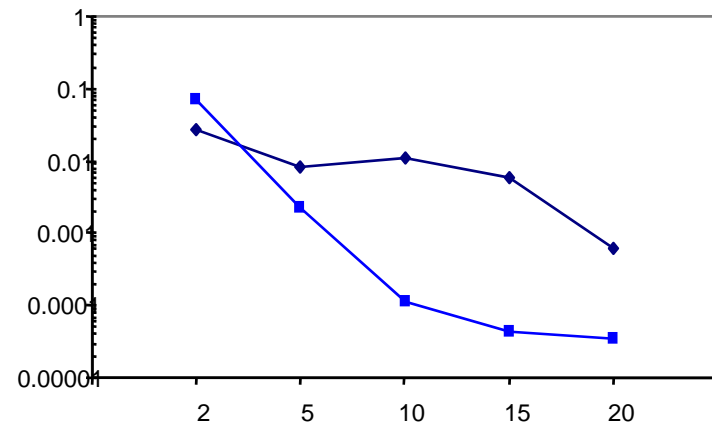
ArH<sup>+</sup>

◆ Calc  
■ Exp



Ar<sup>+</sup>

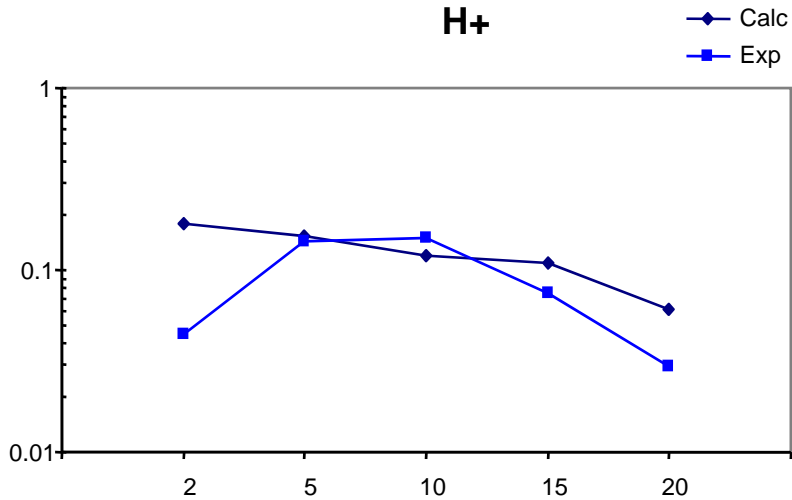
◆ Calc  
■ Exp



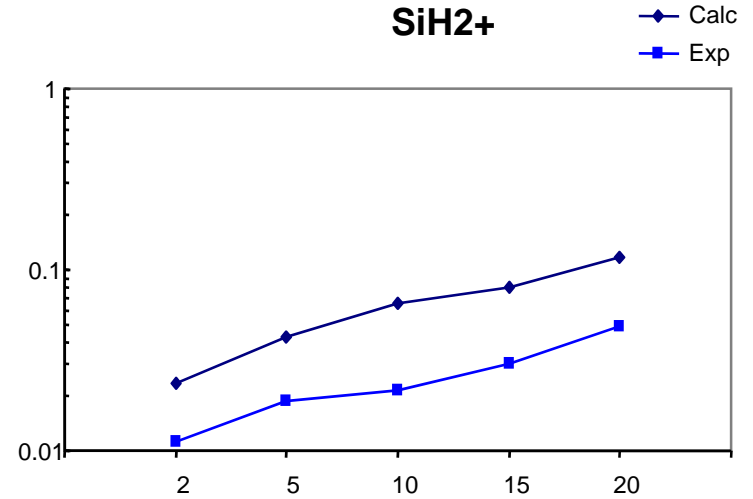


# Last Results – position B

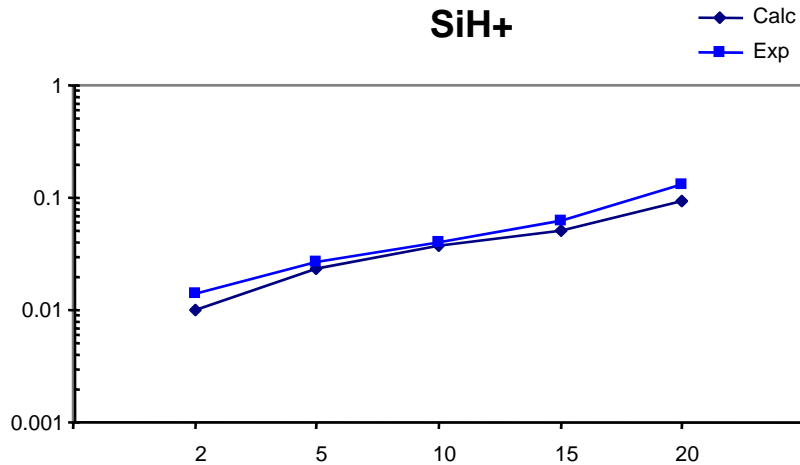
**H+**



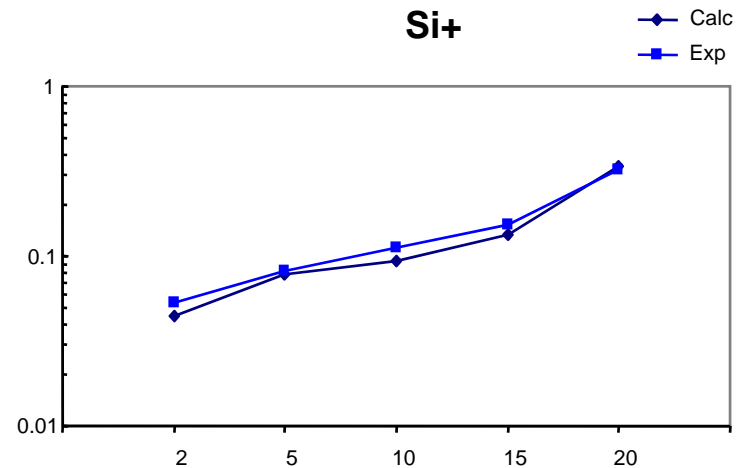
**SiH<sub>2</sub><sup>+</sup>**



**SiH<sup>+</sup>**



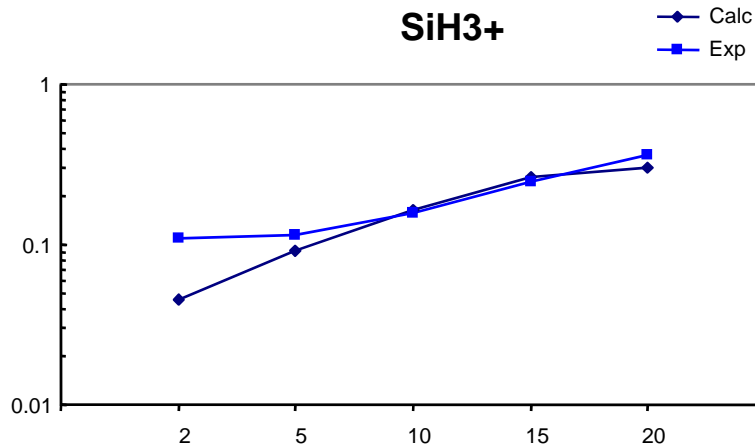
**Si<sup>+</sup>**



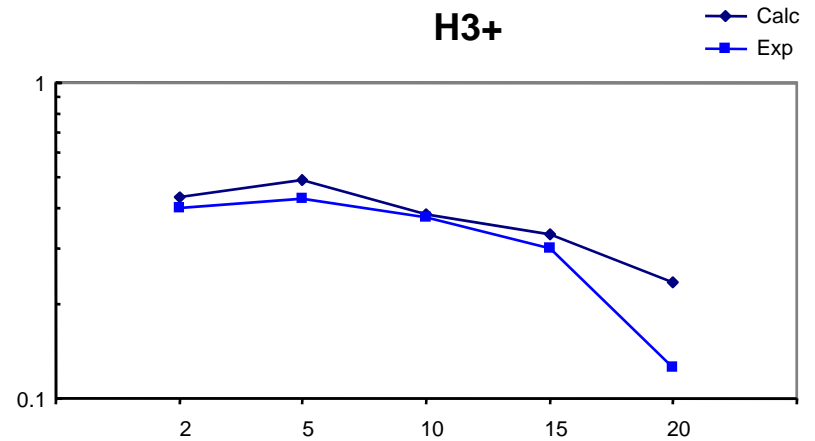


# Last Results – position C

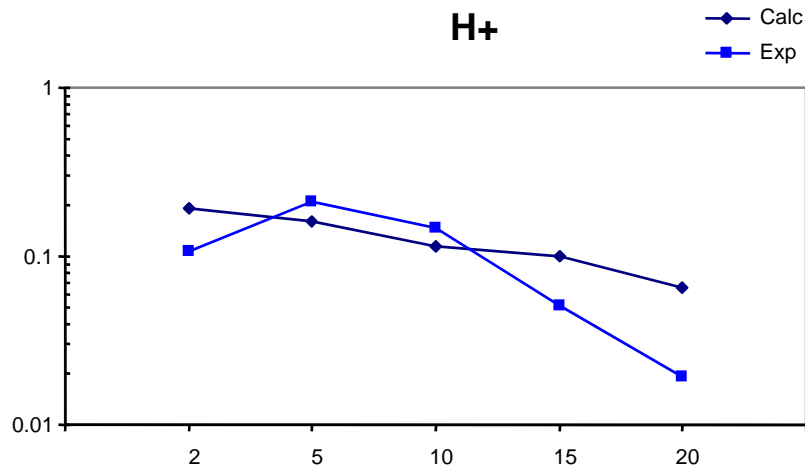
### SiH3+



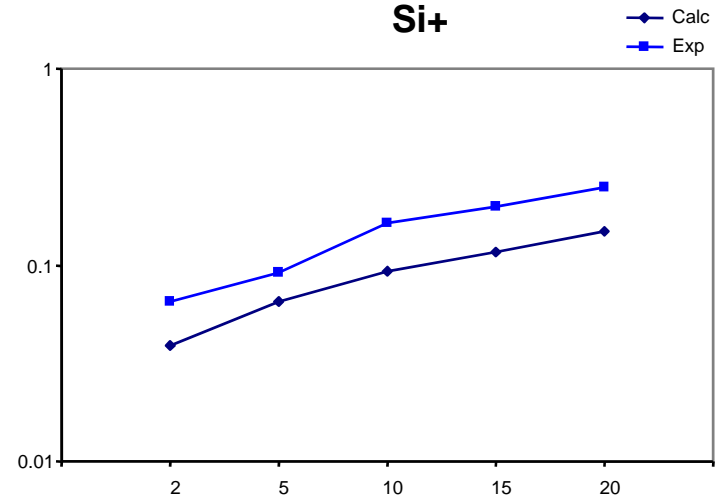
### H3+



### H+



### Si+





# Conclusions

- Ion concentrations in very good agreement with experiments
- Radical concentration in qualitative agreement with Tamara results

